EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L18 | 1 | "20020162827".pn. | US-PGPUB; USPAT | OR | ON | 2009/01/16 22:26 |
| L19 | 59 | ratio same earth same area same wall | US-PGPUB; USPAT | OR | ON | 2009/01/16 22:44 |
| L20 | 14 | 19 and plasma | US-PGPUB; USPAT | OR | ON | 2009/01/16 22:45 |
| L22 | 59 | earth with wall with inner with chamber | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:18 |
| L23 | 29 | 22 and plasma | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:18 |
| L25 | 4 | earth same (wall with inner with chamber) same chip$4 | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:22 |
| L26 | 3192 | (dummy near2 substrate) | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:59 |
| L27 | 6263 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same plasma same ("al" or aluminium or aluminum) | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:59 |
| L28 | 44 | L27 and L26 | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:59 |
| L29 | 8 | L28 and 134/1-1.3.ccls. | US-PGPUB; USPAT | OR | ON | 2009/01/16 23:59 |
| L37 | 1053 | shirayone-shigeru.in. ono-tetsuo.in. itabashi-naoshi. in. yoshigai-motohiko.in. abe-takahiro.in. shimomura-takahiro.in. kitsunai-hiroyuki.in. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/17 00:29 |
| L38 | 7 | 37 and ((clean$3 or etch $3 or treat$3 or remov$3) same (apparatus or chamber) same plasma same (wafer or substrate or semiconductor)) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine)) and ((aluminum or aluminium or "al") with (fluoride or fluorine)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/17 00:29 |

| L39 | 732 | "hitachi high-technologies corporation".as. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/17 00:30 |
|---|---|---|---|---|---|---|
| L40 | 1 | 39 and ((clean$3 or etch $3 or treat$3 or remov$3) same (apparatus or chamber) same plasma same (wafer or substrate or semiconductor)) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine)) and ((aluminum or aluminium or "al") with (fluoride or fluorine)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/17 00:31 |
| S1 | 1070 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:05 |
| S2 | 3192 | (dummy near2 substrate) | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:05 |
| S3 | 13 | S1 and S2 | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:05 |
| S4 | 13 | S3 and plasma | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:05 |
| S5 | 3 | S4 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:05 |
| S6 | 82 | S1 same ("al" or aluminium or aluminum) | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:09 |
| S7 | 43 | S6 same plasma | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:09 |
| S8 | 1 | S7 and S2 | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:09 |
| S9 | 6263 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same plasma same ("al" or aluminium or aluminum) | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:10 |
| S10 | 44 | S9 and S2 | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:10 |
| S11 | 9 | S10 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:10 |

| S12 | 70 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 17:16 |
|-----|----|-----|-----|----|----|-----|
| S13 | 1 | S12 and plasma and (dummy near2 substrate) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 17:16 |
| S14 | 970 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same plasma same ("al" or aluminium or aluminum) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 17:17 |
| S15 | 1 | S14 and plasma and (dummy near2 substrate) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 17:17 |
| S16 | 1 | "4786352".pn. | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:26 |
| S17 | 1 | "6186153".pn. | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:34 |
| S18 | 1 | "20050072444".pn. | US-PGPUB; USPAT | OR | ON | 2009/01/15 17:58 |
| S19 | 1 | "4786352".pn. | US-PGPUB; USPAT | OR | ON | 2009/01/15 19:00 |
| S20 | 628 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) same plasma | US-PGPUB; USPAT | OR | ON | 2009/01/15 19:04 |
| S21 | 36 | S20 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/15 19:04 |
| S22 | 1070 | (clean$3 or etch$3 or treat $3 or remov$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl. sub.2" or chlorine) | US-PGPUB; USPAT | OR | ON | 2009/01/15 19:05 |
| S23 | 82 | S22 same ("al" or aluminium or aluminum) | US-PGPUB; USPAT | OR | ON | 2009/01/15 19:05 |
| S24 | 43 | S23 same plasma | US-PGPUB; USPAT | OR | ON | 2009/01/15 19:05 |

| S25 | 70 | (clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 19:12 |
| S26 | 5 | S25 same ("al" or aluminium or aluminum) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 19:12 |
| S27 | 31 | (clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same ("hbr" or hydrobromic or "hydrogen bromide") same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide") | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 19:16 |
| S28 | 19 | S27 and plasma | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/15 19:17 |
| S29 | 393 | ((clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same ("al" or aluminium or aluminum) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same (gas or plasma)) | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:33 |
| S30 | 38 | S29 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:34 |
| S34 | 210 | ((clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same ("al" or aluminium or aluminum) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so. | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:47 |

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|---|---|---|---|---|---|---|
| | | sub.2" or "sulfur dioxide" or inert)) | | | | |
| S35 | 23 | S34 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:47 |
| S37 | 5 | ((clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same (residu$3 or contaminat$5 or particle) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co. sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide" or inert)) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/16 00:49 |
| S38 | 265 | ((clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same (residu$3 or contaminat$5 or particle) same plasma) and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co. sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide" or inert)) | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:50 |
| S39 | 37 | S38 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:50 |
| S40 | 20 | S39 and @pd< "20040304" | US-PGPUB; USPAT | OR | ON | 2009/01/16 00:51 |
| S41 | 23 | ("4376672" \| "5298790" \| "5423941" \| "5585012" \| "5756400" \| "5814563"). PN. OR ("6318384"). URPN. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/01/16 14:10 |

| S43 | 2 | S41 and (("hbr" or hydrobromic or "hydrogen bromide") same ("cl.sub.2" or chlorine) same ("n.sub.2" or nitrogen or "co" or "carbon monoxide" or "co.sub.2" or "carbon dioxide" or "h.sub.2" or hydorgen or "so.sub.2" or "sulfur dioxide" or inert)) | US-PGPUB; USPAT; USOCR | OR | ON | 2009/01/16 14:11 |
| S44 | 1 | "6136211".pn. | US-PGPUB; USPAT; USOCR | OR | ON | 2009/01/16 14:37 |
| S48 | 3 | ((clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same (residu$3 or contaminat$5 or particle) same plasma) and ("sicl.sub.4" or Tetrachlorosilane) | FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/01/16 15:06 |
| S49 | 396 | ((clean$3 or etch$3 or treat$3 or remov$3) same (apparatus or chamber) same (residu$3 or contaminat$5 or particle) same plasma) and ("sicl.sub.4" or Tetrachlorosilane) | US-PGPUB; USPAT | OR | ON | 2009/01/16 15:07 |
| S50 | 42 | S49 and "134".clas. | US-PGPUB; USPAT | OR | ON | 2009/01/16 15:08 |

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